

Development of PVD-coated and nanostructured reactive multilayer films

Seema Sen



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Cover Image:

Left: SEM image of freestanding ternary Ti/Si/Ti/Al reactive multilayer film.
/ Middle: Colored TEM image of Zr/Al binary reactive film. / Right: High speed photographic image of steady state reaction propagation in Ti/Si/Ti/Al reactive film (top) and unsteady propagation in Ti/3Al reactive film (bottom).

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